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(54) **Coarse and fine projective optical metrology system**

(57) Described herein is a projective optical metrology system including: a light target (2) formed by a first number of light sources (4a-4c) having a pre-set spatial arrangement; and an optical unit (6) including an optoelectronic image sensor (10), which receives a light signal (R_1 , R_2) coming from the light target (2) and defines two different optical paths for the light signal towards the op-

toelectronic image sensor (10). The two optical paths are such that the light signal forms on the optoelectronic image sensor at most an image ($I_1; I_2$) of the light target that can be processed for determining at least one quantity indicating the mutual arrangement between the light target and the optical unit.

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